

Abstract

The invention provides a method for producing a quartz glass jig for use in
5 semiconductor industries, which enables increasing the surface layer cleanliness simply and
surely at low cost; it also provides a quartz glass jig improved in surface layer cleanliness.
The inventive means for resolution are a method comprising processing a quartz glass raw
material into a desired shape by a treatment inclusive of fire working, annealing for stress
removal, and cleaning treatment to obtain the final product, the method is characterized by
10 that it comprises performing gas phase etching step and gas phase purification step on the
surface layer of the quartz glass jig after applying the annealing treatment for stress removal
but before the cleaning treatment, wherein the gas phase purification step is carried out
continuously after the gas phase etching step.

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